



भारतीय प्रौद्योगिकी संस्थान इन्दौर

खण्डवा रोड, सिमरोल  
इन्दौर ४५३ ५५२, भारत

Indian Institute of Technology Indore

Khandwa Road, Simrol  
Indore 453 552, India

Office: +91-7324-306526  
E-mail: rupesh@iiti.ac.in

IIT Indore

**Dr. Rupesh Devan**  
Metallurgy Engineering and Materials Science

In our lab, SONICA Ultrasonic Cleaner is used for a variety of applications. One important application is the cleaning of transparent conductive oxide (TCO) coated glass substrates. Cleaning of substrates is given utmost importance in optoelectronic devices.

When glass sheets are prepared, grease is used to ensure zero sticking between successive glass sheets on the conveyor belts. However, the complete removal of grease is a primary requirement when these TCO coated glass sheets are used in optoelectronic devices.

For this purpose at Nanostructures and Device Fabrication lab, we use SONICA Ultrasonic Cleaner in Timed Mode of operation. We ultrasonically clean TCO substrates with DI Water, Ethanol, Acetone, Isopropyl alcohol.

Apart from the above-mentioned application, SONICA Ultrasonic Cleaner is used in dissolving low soluble solutes in the required solvents. To ensure proper dissolution along with timed mode, the bath temperature is raised and sonicated.

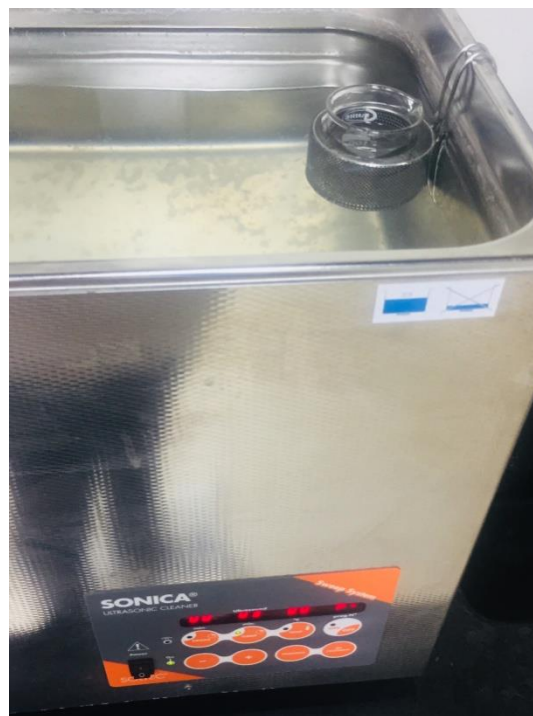


Figure 1. Top view of SONICA Ultrasonic Cleaner used for dissolving low soluble solutes at Nanostructures and Device Fabrication lab. IIT Indore, Madhya Pradesh, India.

*Rupesh*



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Figure 2. Top view of SONICA Ultrasonic Cleaner used for cleaning substrates at Nanostructures and Device Fabrication lab. IIT Indore, Madhya Pradesh, India.

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